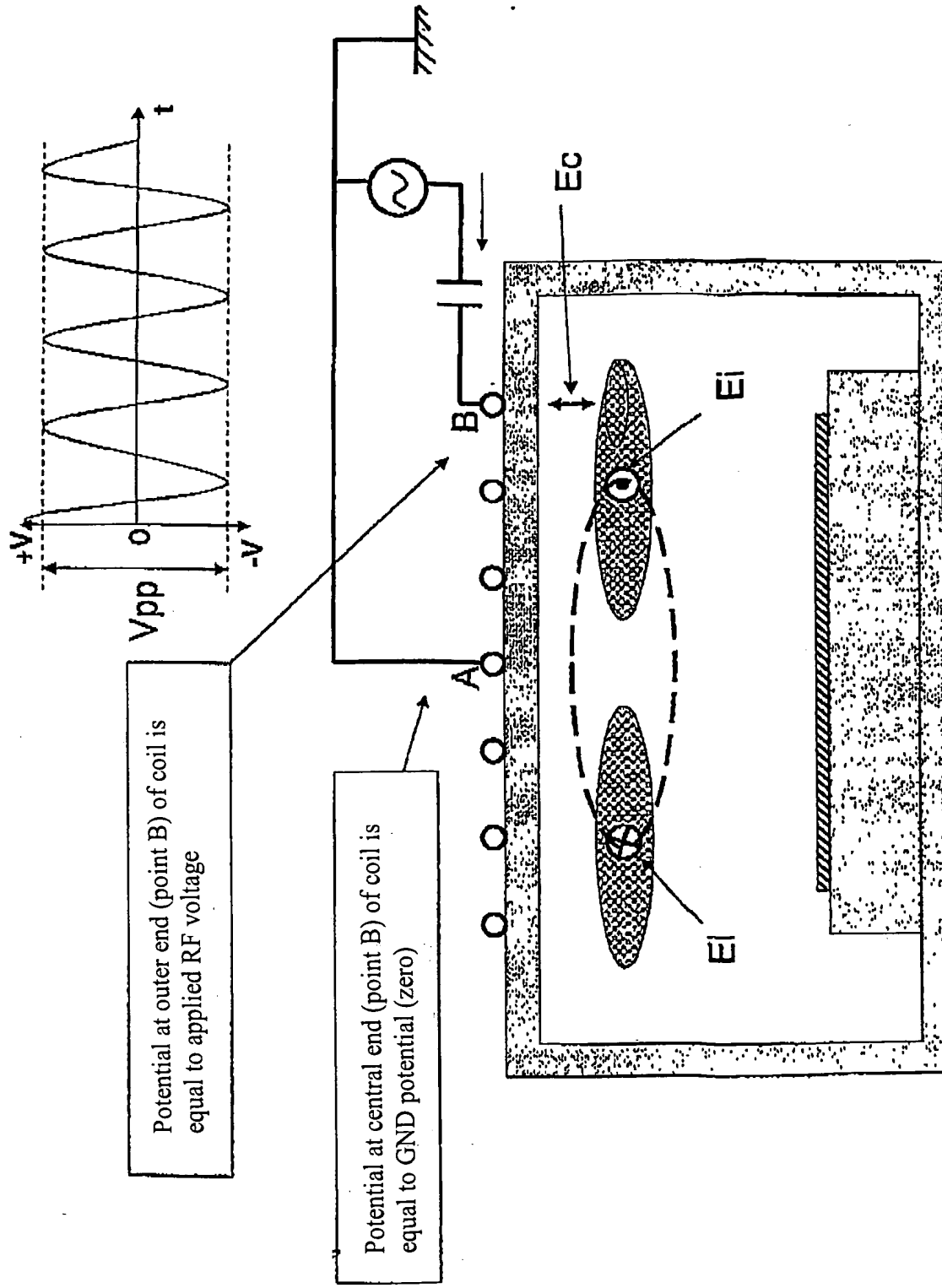
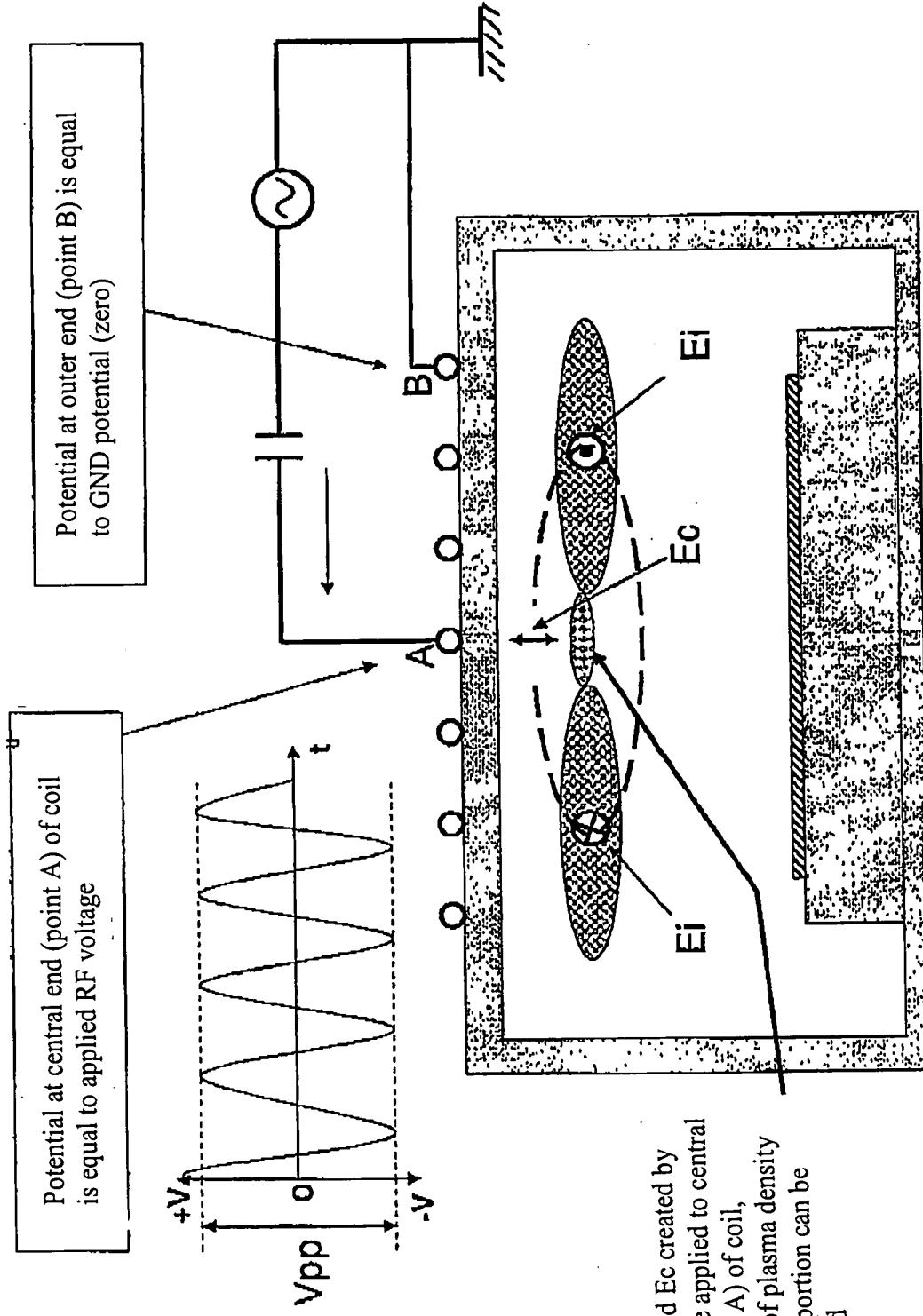


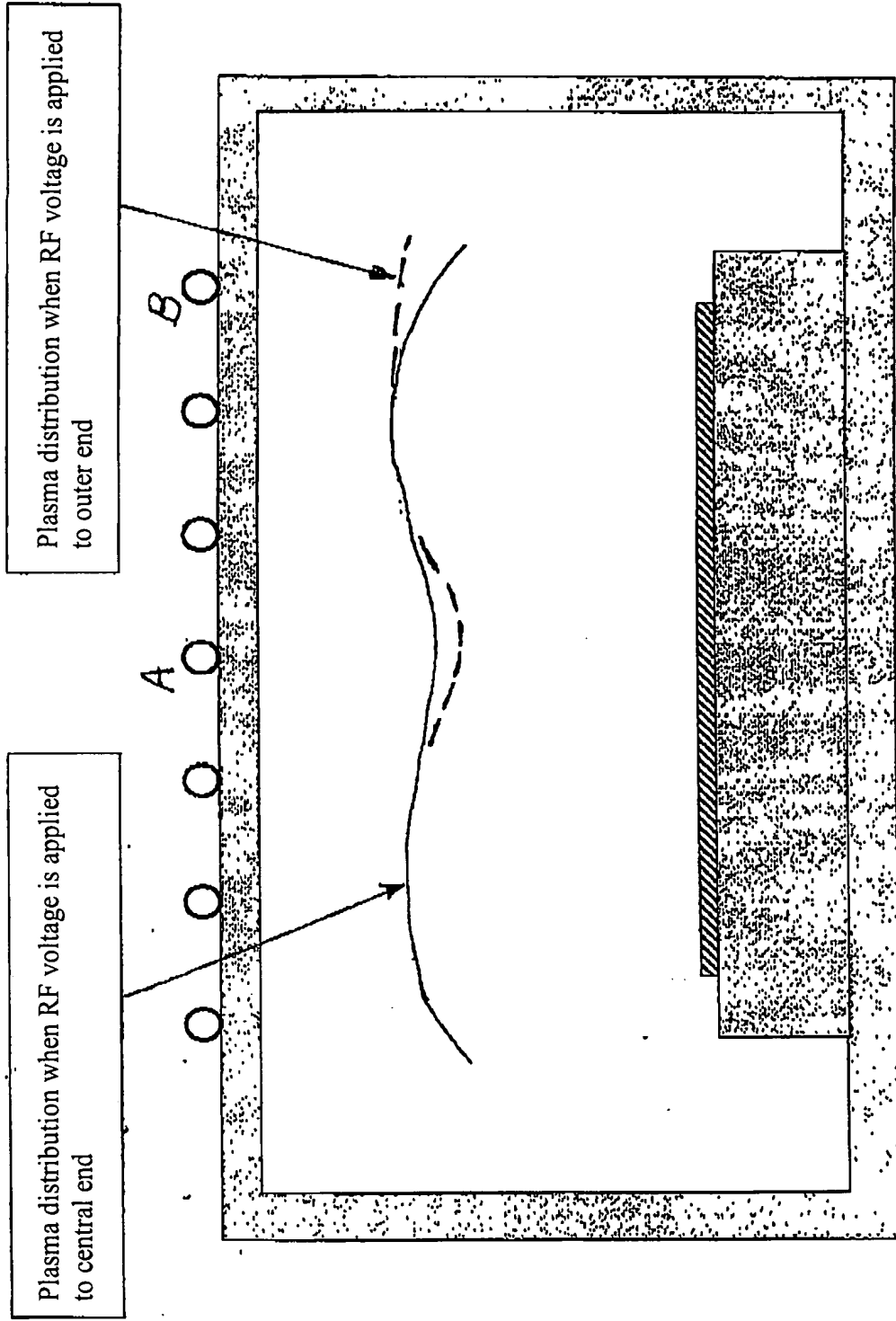
When applying RF voltage to outer end of spiral coil



Due to field E_c created by RF voltage applied to outer end (point B) of coil, plasma distribution of outer portion may be biased

When applying RF voltage to central end of spiral coil





Conceptual Diagram of plasma distribution when RF voltage is applied to central end and outer end of spiral coil